# **Supporting Information**

## Effective Charge Separation of Inverted Polymer Solar Cells using Versatile MoS<sub>2</sub> Nanosheets as Electron Transport Layer

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<sup>&</sup>lt;sup>+</sup> Electronic supplementary information (ESI) available: additional topographic images, and additional ADF and ABF images, and additional UPS data of PEIE/ITO/glass, and additional energy band diagram.

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#### 1. Experimental

**1. 1. Exfoliation of MoS<sub>2</sub> Nanosheets:** 2 g of the commercial MoS<sub>2</sub> sheets (2D semiconductor) was dispersed in 1 L of ethanol. The MoS<sub>2</sub> dispersion was treated by tip-sonication for 5 hours. Then, the MoS<sub>2</sub> dispersion was centrifuged for 30 min at 8000 rpm to collect a supernatant and remove precipitation. The initial concentration of the MoS<sub>2</sub> NS supernatant was  $100 \pm 2.7$  mg/L. Then, the supernatant was diluted in 1mL of ethanol and the concentration was estimated to be about 16.67 mg/L.

1. 2. Characterization of MoS<sub>2</sub> Nanosheets: The MoS<sub>2</sub> NSs were characterized through TEM, AFM, Raman spectroscopy, UV-vis absorption spectroscopy, and PL spectroscopy. The TEM images were obtained using a Philips Tecnai G2 F20 TEM microscope with an accelerating voltage of 200 kV. The AFM surface images and height distribution were measured by Park system NX10. The MoS<sub>2</sub> NSs solution in DMF was deposited on a silicon wafer by spin coating and drying under ambient conditions. The AFM image was obtained in a tapping mode. Different concentrations of MoS<sub>2</sub> NSs solution were used to achieve layers deposited on SiO<sub>2</sub>/Si substrate. Raman spectra of MoS<sub>2</sub> NSs were obtained using a Horiba Jobin Yvon-Labram HR UV visible NIR Raman microscope spectrometer with a 514 nm Ar laser. Ultraviolet-visible (UV-vis) absorption spectra of the MoS<sub>2</sub> NSs measured with a Shimadzu, UV-2600 UV-vis spectrophotometer. PL spectra were obtained using a Horiba NanoLog-C. To demonstrated the MoS<sub>2</sub> NSs of energy levels using electrochemical cyclic voltammetry. MoS<sub>2</sub> NSs were dispersed in a 0.5% Nafion solution (isopropanol and dimethylformamide) and dropped on glassy carbon electrode to serve as the working electrode. The counter electrode and the reference electrode were platinum wire and Ag/AgNO<sub>3</sub> (in 0.01 M MeCN), respectively, and the electrolyte was a

solution of 0.1 M tetrabutylammonium phosphorus hexa fluoride (TBAPF6) in anhydrous acetonitrile. Measurements were performed at room temperature with a scan rate of 100 mV/s.

**1.3. Device fabrication process of iPSCs:**  $1.5 \times 1.5$  cm<sup>2</sup> patterned ITO-coated glass substrates were cleaned with acetone, ethanol, and 2-propanol, respectively. The ITO-coated glass was treated with O<sub>2</sub> plasma for 40 sec. PEIE layer was spin-coated on the ITO-coated glass at 4000 rpm for 40 sec, and the substrate was annealed at 110 °C for 10 min. After annealing, 0.1 ml of MoS<sub>2</sub> NSs in 1 ml of ethanol solution was spin-coated on the PEIE surface at 4000 rpm for 40 sec, followed by annealing at 140 °C for 10 min under ambient conditions. The substrates were transferred into a nitrogen-filled glove box. The blend of P3HT:PC<sub>60</sub>BM (1.5:1 (by weight)), PTB7:PC<sub>71</sub>BM (1:1.5 (by weight)), PTB7-Th:PC<sub>71</sub>BM (1:1.5 (by weight)) solution were spin-coated onto the MoS<sub>2</sub> NSs interlayer at 2000 rpm for 10 sec and 1400 rpm for 10 sec, respectively. Finally, MoO<sub>3</sub> (10 nm) and Ag (80 nm) were deposited by thermal evaporation on the active layer under a pressure of 1x10<sup>-6</sup> Torr.

**1. 4. Characterization of iPSCs structures:** The structures of iPSCs with the MoS<sub>2</sub> NSs/PEIE/ITO/glass were characterized through Focused Ion Beam (FIB), TEM and STEM-EDS. In detail, The FIB was applied for cross-sectional sample preparation of iPSCs with both TEM and STEM-EDS. Thinly sliced TEM samples were prepared using a FIB (Nova nanolab 600 Dual Beam) operating at 5~20 kV with Ga ions. The TEM images were obtained using a Philips Tecnai G2 F20 TEM microscope with an accelerating voltage of 200 kV. The STEM-EDS images were obtained using a JEM-ARM200F Cs-corrected STEM.

**1. 5. Photovoltaic device characterization of iPSCs with/without MoS<sub>2</sub> Nanosheets:** The iPSCs were then tested in air under an AM 1.5 G illumination of 100 mW/cm<sup>2</sup> (Oriel 1 kW solar

simulator), which was calibrated with the International System of Units (SI) (SRC-1000-TC-KG5-N, VLSI Standards, Inc) for accurate measurement. The external quantum efficiency (EQE) was measured using an Oriel IQE-200 (Newport), a calibrated Si UV detector and an SR8570 low noise current amplifier. In TCSPC, photo-excitation was carried out by the mode-locked titanium: sapphire laser with the wavelength of 400 nm and luminescence signals were detected by an InGaAs based photomultiplier detector.

2. The topographic images of MoS<sub>2</sub> NSs and line profile.



Figure S1. Topographic images and line profiles of the  $MoS_2$  NSs before (a) and (c) after tipsonication exfoliation and centrifugation process (b) and (d) corresponding to the white line in the topographic images.

3. The topographic images of  $SiO_2$  on Si substrate and PEIE on  $SiO_2$  on Si substrate.



**Figure S2.** Topographic images RMS values of the  $SiO_2$  on Si (a) and PEIE on  $SiO_2$  on Si substrate (b).

4. The annular dark field (ADF) and annular bright field (ABF) images of the MoS<sub>2</sub> NSs on the PEIE/ITO/glass.



**Figure S3.** The annular dark field (ADF) and annular bright field (ABF) images of the MoS<sub>2</sub> NSs.

We performed image analysis of  $MoS_2$  NSs by a spherical aberration-corrected scanning TEM (Cs-TEM). As shown in Fig. S2(a) and S2(b), we show the annular dark field (ADF) and annular bright field (ABF) images of the  $MoS_2$  NSs and the ITO/glass substrate. Through the ADF and ABF images, the contrast of the  $MoS_2$  NSs layer was improved by confirming the shape of the  $MoS_2$  NSs. As a result,  $MoS_2$  NSs applied as ETL could be clearly confirmed.

5. The work function ( $\Phi$ ) of the spin-coated PEIE onto ITO/glass and ITO/glass calculated by using an ultraviolet photoelectron spectroscopy (UPS).



Figure S4. The work function of the PEIE/ITO/Glass and ITO/Glass.

The work function value of the ITO, PEIE/ITO structures obtained 4.29 eV, 3.36 eV, respectively. In this structure, the PEIE layer plays a role as a surface modifying layer on the ITO layer for good electron selectivity and efficiently promotes electron transportation to decrease the work function of ITO due to the formation of dipole layer.<sup>1</sup>

6. Energy level diagram of the iPSCs with the MoS<sub>2</sub> interlayer highlighting pathways for charge generation and transport.



Figure S5. Energy level diagrams of the inverted PSCs with the MoS<sub>2</sub> interlayer.

The energy level diagrams of iPSCs demonstrate the possible pathways of current generation and transportation after the excitation of the photoactive materials  $P3HT:PC_{60}BM$  (a) and PTB7-th:PC<sub>71</sub>BM (b).<sup>2</sup>

7. The structure of optical absorption simulation.



Figure S6. The structure of optical absorption simulation.

The solar cell structure used for the simulation is the Ag (80 nm)/MoO<sub>3</sub> (10 nm)/PTB7:PC<sub>71</sub>BM (120 nm)/MoS<sub>2</sub> (8.31 nm)/PEIE (3 nm)/ITO (150 nm)/glass (1.1 mm) structures. MoS<sub>2</sub> NS diameter: 25 nm and spacing between the edges of MoS<sub>2</sub> NS: 104 nm

### Reference

- (1) Hu, Z.; Wu, Z.; Han, Cheng.; He, J.; Ni, Z.; Chen, W. Two-dimensional transition metal dichalcogenides: interface and defect engineering. *Chem. Soc. Rev.* **2018**, *47*, 3100-3128.
- (2) Chen, W.; Qi, D.; Gao, X.; Wee, A. T. S. Surface transfer doping of semiconductors. *Prog. Surf. Sci.* 2009, 84, 279-321.